

## EE 330 Homework 5 Solutions Fall 2025

1. Length of interconnect =  $120\ \mu m$

Width of interconnect =  $0.6\ \mu m$

No. of squares =  $400/2 = 200$

Sheet resistance of interconnect =  $23.5\ \Omega/sq$

Resistance =  $23.5 * 200 = 4.7\ k\Omega$

Capacitance from interconnect to substrate

Capacitance of Poly 1 substrate from the table given =  $84\ aF/\mu m^2$

Interconnect area =  $0.6\ \mu m * 120\ \mu m = 72\ \mu m^2$

Capacitance of the substrate =  $84\ aF/\mu m^2 * 72\ \mu m^2 = 6.048\ fF$

Capacitance between metal and interconnect

Capacitance of Poly and Metal1 from the table given =  $56\ aF/\mu m^2$

Area of contact between poly and metal =  $72\ \mu m^2$

Capacitance =  $56\ aF/\mu m^2 * 72\ \mu m^2 = 4.032\ fF$

2. Length of the interconnect =  $200\ \mu m$

Width of interconnect =  $2\ \mu m$

No. of squares =  $200/2 = 100$

Resistance =  $20\ \Omega$

Sheet resistance =  $20/100 = 0.2\ \Omega/sq$

Resistivity of copper =  $17.2\ n\Omega * m$

Thickness = Resistivity/Resistance =  $86\ nm$

For Ag =>

Resistivity of silver =  $15.9\ n\Omega * m$

Sheet resistance = Resistivity /thickness =  $15.9\ n\Omega * m / 86\ nm = 0.185\ \Omega/sq$

Length =  $W*R/Rs = 216.4\ \mu m$

3.

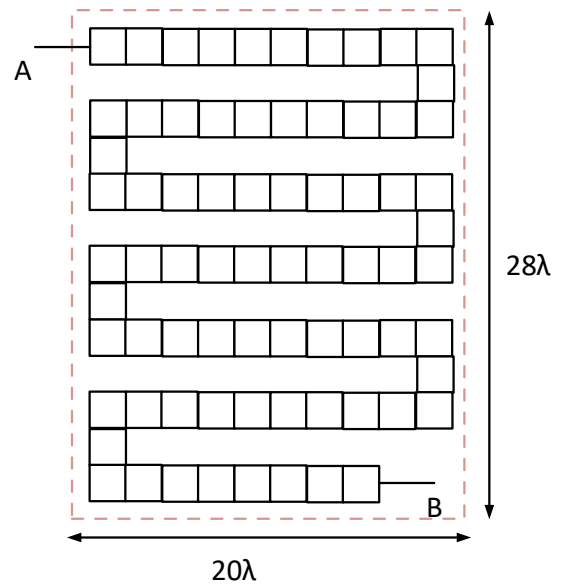
Overlap Cap			
Layers	Overlap Area ( $\mu m^2$ )	$aF/\mu m^2$	Cap ( $aF$ )
Poly-Sub	89.1	84	7484.4
M1- Sub	4.86	27	131.22
M2-sub	15.12	12	181.44
M3-Sub	5.4	7	37.8
M1-Poly	24.3	56	1360.8
M2-Poly	25.92	15	388.8
M3-Poly	12.42	9	111.78
M2-M1	9.72	31	301.32
M3-M1	4.86	13	63.18
M3-M2	6.48	35	226.8
Fringe Cap			
Layers	Length ( $\mu m$ )	$aF/(\mu m)$	Cap (af)
Poly-Sub	37.8	0	0
M1- Sub	9	49	441
M2-sub	15.6	33	514.8
M3-Sub	9.6	23	220.8
M1-Poly	5.4	59	318.6
M2-Poly	7.2	38	273.6
M3-Poly	3.6	28	100.8
M2-M1	5.4	51	275.4
M3-M1	3.6	34	122.4
M3-M2	7.2	52	374.4

4. Sheet resistance for high resistance poly =  $44\Omega/\square$

Resistance =  $3000\Omega$

No. of squares =  $3000/44 = 68$

$L = 3W$ ; Let's use a  $2\lambda \times 2\lambda$  for one square. The following layout is approximately 68 squares and the bounding rectangle meets the aspect ratio requirements.

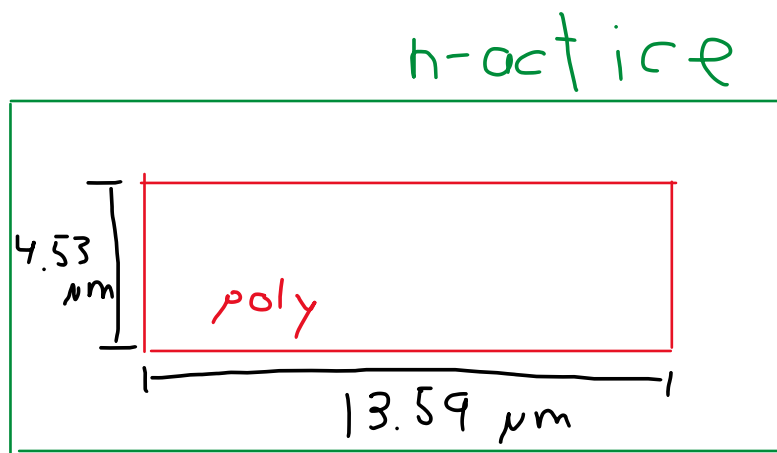


Problem 5.

Using  $N^+$  active and Poly 1. Since this has the highest capacitance.

Capacitance of :  $C_{N+_{Poly}} = 2434 \text{ aF}/\mu\text{m}^2$

Area of Capacitance:  $(C = C_d * A) : A = C/C_d = 150 \text{ fF} / 2434 \text{ aF}/\mu\text{m}^2 = 61.63 \mu\text{m}^2$



# Problem 6

$$\text{Nominal Value of resistance} = \rho \cdot \frac{\text{Length}}{\text{Area}}$$

From table/calculator relating  $\rho$  to resistivity

$$\rightarrow \rho = 22.34 \Omega \cdot \text{cm} = 22.34 \times 10^{-2} \Omega \text{m}$$

$$\rightarrow \text{height (thickness)} = 0.1 \mu\text{m}$$

$$\rightarrow \text{Area} = 0.4 \mu\text{m}^2$$

$$\text{Length} = 50 \mu\text{m}$$

$$\Rightarrow \text{Nominal Value of resistance} = \frac{50}{0.4 \times 10^{-6}} \times 22.34 \times 10^{-2}$$

$$= 27.925 \text{ M}\Omega$$

## 7. Part A:

Begin by calculating the number of squares in each serpentine structure. We can calculate the number of horizontal lines in the serpentine structures as follows:

$$N_{\text{Horizontal}} = \frac{\text{Length}_{\text{die}}}{\text{Width}_{\text{Interconnect}} + \text{Width}_{\text{Spacing}}} \cdot \frac{1 \text{cm}}{0.2 \mu\text{m}} = 50000$$

So we have 50,000 horizontal lines, each 1cm long. This amounts to  $5 \times 10^9$  squares.

To connect these lines, we have  $N_{\text{Horizontal}} - 1$  vertical segments, each  $0.1 \mu$  wide. This amounts to 49,999 squares.

In total, we have  $5 \times 10^9 + 49999$  squares per resistor. Each metal layer has a resistivity of  $0.12 \Omega/\text{sq}$ , so each resistor has a resistance of  $600 \text{ M}\Omega$ . When combined in parallel, we have a resistance of  $200 \text{ M}\Omega$ .

Part B:

Each resistor is only  $0.1\mu\text{m}$  thick, so each can carry a maximum density of  $150\mu\text{A}$ . Placed in parallel, this means the total resistor can carry up to  $450\mu\text{A}$ .

Part C:

$$P = I^2 R = [450\mu\text{A}]^2 [200\text{M}\Omega] = 40.5\text{W}$$

Problem 8 If the resistance in the interconnect is neglected, it acts as a capacitor in parallel with the input capacitance of the second inverter.  $C_{\Sigma} = (C_D)(WL)$

$$\begin{aligned} \text{a) } R_{PD} &= 2\text{K} & t_{HL} &= R_{PD}(C_L) & C_D &= 27\text{af}/\mu^2 \\ C_{\Sigma} &= (0.6\mu)^2 (27\text{af}/\mu^2) \\ &= 9.7\text{aF} \end{aligned}$$

$$C_L = 3\text{fF} + 9.7\text{aF} \approx 3.01\text{fF}$$

$$\therefore t_{HL} \approx 6.02\text{psec}$$

$$\text{b) If } L = 200\mu$$

$$C_{\Sigma} = (0.6)(200) 27\text{af}/\mu^2 = 3.24\text{fF}$$

$$\therefore C_L = 3\text{fF} + 3.24\text{fF} = 6.24\text{fF}$$

$$\therefore t_{HL} = (2\text{K})(6.24\text{fF}) = 12.5\text{psec}$$

c) The only change with poly (again neglecting the interconnect resistance) is

$C_D = 84\text{af}/\mu^2$  so  $C_{\Sigma} = (0.6)(200)84\text{af}/\mu^2 = 10.1\text{fF}$  so  $C_L = 13.1\text{fF}$  and thus

$$t_{HL} = (2\text{K})(10.1\text{fF}) = 20.2\text{psec}$$